

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

|                              |   |                                      |
|------------------------------|---|--------------------------------------|
| In re Patent Application of  | ) | Attorney Docket No.: <b>SOEI0021</b> |
|                              | ) |                                      |
| Ken SAWABE et al.            | ) | Confirmation No. 9014                |
|                              | ) |                                      |
| Serial No.: 10/595,920       | ) | Group Art Unit: 1795                 |
|                              | ) |                                      |
| Filed: May 19, 2006          | ) | Examiner: P. THOMPSON-RUMMEL         |
|                              | ) |                                      |
| For: PHOTSENSITIVE RESIN     | ) | Date: May 2, 2008                    |
| COMPOSITION, PHOTSENSITIVE   | ) |                                      |
| ELEMENT, RESIST PATTERN      | ) |                                      |
| FORMING METHOD AND PROCESS   | ) |                                      |
| FOR PRODUCING PRINTED WIRING | ) |                                      |
| BOARD                        | ) |                                      |

**AMENDMENT (C) AFTER FINAL**

United States Patent and Trademark Office  
Customer Service Window, Mail Stop RCE  
Randolph Building  
401 Dulany Street  
Alexandria, VA 22314

Sir:

In response to the Final Office Action mailed February 4, 2008, and in view of the Request for Continued Examination (RCE) filed herewith, please amend the application identified above as follows:

**Amendments to the Claims** are reflected in the listing of claims that begins on page 2 of this paper.

**Remarks/Arguments** begin on page 8 of this paper.